

Message Text

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64

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TO USMISSION OECD PARIS PRIORITY

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EXCON

EO 11652: XGDS-1

TAGS: ESTC, COCOM, UK, PL

SUB:US SEMICONDUCTOR MANUFACTURING EQUIPMENT TO POLAND -
IL 1355

REF : COCOM DOC(73)933

OECD PARIS 18210

1. FOLLOWING ARE REPLIES TO UK QUESTIONS PARA 1 REF. B:

A. PRODUCTION RATE CALCULATIONS MADE BY US FIRM USING
THEIR SIMILAR FACILITIES AS A GUIDE SHOW THAT SEVEN THREE-
TUBE DIFFUSION FURNACES ARE REQUIRED TO PRODUCE 100,000
THRISTORS AND 100,000 RECTIFIERS PER YEAR.

B AND C. OUTPUT RATES PER DIFFUSION FURNACE DEPEND ON THE
TUBE DIAMETER, NUMBER OF SLICES PER DIFFUSION LOAD AND TIME
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FOR DIFFUSION OR CYCLE TIME. THE FURNACES PROPOSED FOR

EXPORT TO POLAND ARE CALCULATED TO BE USED 24 HOURS A DAY
FOR 21 WORK DAYS PER MONTH TO YIELD A PRODUCT MIX OF 100,000
THYRISTORS AND 100,000 RECTIFIERS PER YEAR.

D. EQUIPMENT PROVIDED IN PLANT PACKAGE IS NOT CAPABLE OF
MAKING MASKS, ONLY MASK DUPLICATION. EQUIPMENT CONSISTS
OF BASICALLY A MASK PRINTER AND DEVELOPER STATION. ORIGINAL
MASKS WILL BE SUPPLIED BY APPLICANT FROM THE US. IF IC
MASKS WERE MADE AVAILABLE, THEY COULD BE DUPLICATED USING
EQUIPMENT INCLUDED IN THIS PLANT PACKAGE. HOWEVER,
THYRISTOR AND RECTIFIER MASKS ARE CRUDE IN COMPARISON
TO IC MASKS. IN GENERAL BETTER DUPLICATING EQUIPMENT WOULD
BE USED FOR IC MASK DUPLICATION.

2. RE LAST SENTENCE PARA 3 REF. B, UNITS BEING SUPPLIED IF
FULLY UTILIZED WILL MEET THE PLANNED PRODUCTION OF
THIS FACILITY. RUSH

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